

NOTES:

1. SUBSTRATE: UV FUSED SILICA
2. SURFACE S2 TO BE PARALLEL WITH SURFACE S1 TO WITHIN 5 arcsec
3. COATING (APPLY ACROSS COATING APERTURE)

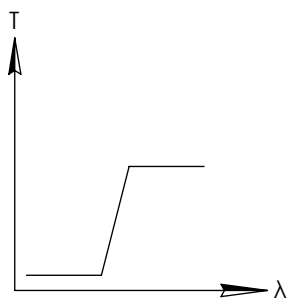
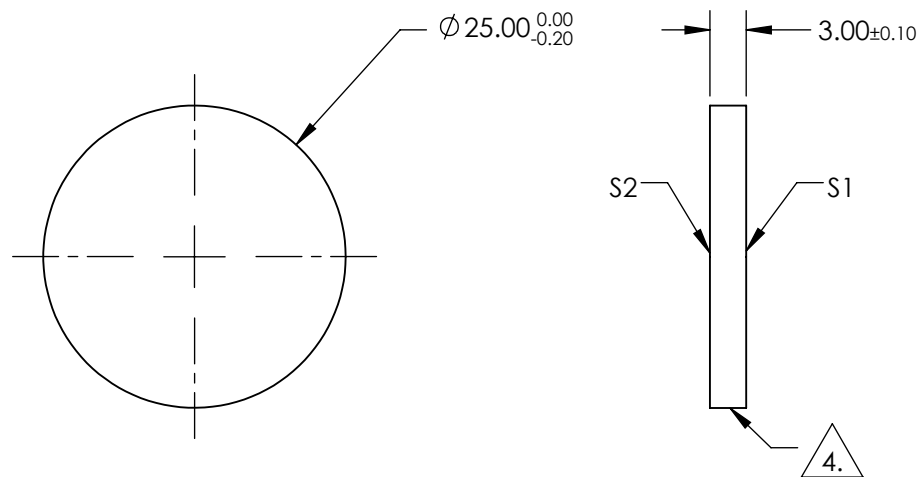
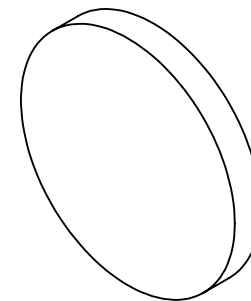
S1: HARD DIELECTRIC SPUTTERED  
 T(avg): ≥91% FROM 560 - 1650nm @ 0° AOI  
 T(avg): ≤0.01% FROM 200 - 539nm @ 0° AOI  
 T(abs): =50% FOR 550±5.5nm @ 0° AOI

S2: SINGLE LAYER MgF2

4. FINE GRIND SURFACE

5. POWER, IRREGULARITY, AND SURFACE QUALITY SPECIFICATIONS APPLY ACROSS CLEAR APERTURE
6. TRANSMITTED WAVEFRONT DISTORTION, RMS: ≤λ/4 @ 633nm
7. ROHS COMPLIANT

FOR INFORMATION ONLY:  
DO NOT MANUFACTURE  
PARTS TO THIS DRAWING



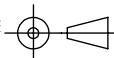
LONGPASS FILTER

SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE  
 DIMENSIONS ARE FOR REFERENCE ONLY

	S1	S2
SHAPE	PLANO	PLANO
SURFACE QUALITY	60-40	60-40
CLEAR APERTURE	>80%	>80%
BEVEL	PROTECTIVE AS NEEDED	PROTECTIVE AS NEEDED

**EO**® Edmund Optics®

THIRD ANGLE PROJECTION



TITLE

Ø25mm, 550nm, HIGH PERFORMANCE  
LONGPASS FILTER

ALL DIMS IN

mm

DWG NO

62984

SHEET  
1 OF 1